

ABSTRACT OF THE DISCLOSURE

A substrate treatment apparatus for removing an unnecessary substance from a surface of a substrate. The apparatus is provided with: an oxidation liquid supply
5 mechanism for supplying an oxidation liquid having an oxidative effect to the substrate surface; a physical cleaning mechanism for physically cleaning the substrate surface; and an etching liquid supply mechanism for supplying an etching liquid having an etching effect to
10 the substrate surface. It is preferred to physically clean the substrate surface while supplying the oxidation liquid to the substrate surface.